

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	4613	438/424.ccls. 438/478.ccls. 438/479.ccls. 438/482.ccls. 438/488.ccls. 438/753.ccls. 216/99.ccls.	US-PGPUB; USPAT	OR	OFF	2005/12/16 12:38
L3	54	L2 and ((silicon si polysilicon poly) same (fluorine fluoride hf hydrofluoric "nh.sub.4f" "nh.sub.4 f" hydroxide ammonium tmah "nh. sub.4oh" "nh.sub.4 oh") same ph)	US-PGPUB; USPAT	OR	ON	2005/12/16 12:59
L4	1	"6276196".pn.	US-PGPUB; USPAT	OR	OFF	2005/12/16 13:00
L5	1	"6202480".pn.	US-PGPUB; USPAT	OR	OFF	2005/12/16 13:00
S1	2	"5155058".pn. "5650043".pn.	US-PGPUB; USPAT	OR	OFF	2005/12/13 15:01
S2	488	438/753.ccls.	US-PGPUB; USPAT	OR	OFF	2005/12/13 15:09
S3	4603	438/424.ccls. 438/478.ccls. 438/479.ccls. 438/482.ccls. 438/488.ccls. 438/753.ccls. 216/99.ccls.	US-PGPUB; USPAT	OR	OFF	2005/12/15 17:49
S4	23	("2902419" "3434896" "3480474" "3505132" "3506509" "3846198" "3909325" "4061783" "4061784" "4137123" "4490181" "4579591").PN. OR ("4859280").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/12/13 16:19
S5	7	("3434896").URPN.	USPAT	OR	OFF	2005/12/13 16:35
S6	7	("3434896").URPN.	USPAT	OR	OFF	2005/12/13 17:01
S7	1	"4352724".pn.	US-PGPUB; USPAT	OR	OFF	2005/12/13 17:02
S8	1	"5650043".pn.	US-PGPUB; USPAT	OR	OFF	2005/12/13 17:02
S9	3	("4482443" "5348627").PN. OR ("5650043").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/12/13 17:02
S10	4613	438/424.ccls. 438/478.ccls. 438/479.ccls. 438/482.ccls. 438/488.ccls. 438/753.ccls. 216/99.ccls.	US-PGPUB; USPAT	OR	OFF	2005/12/15 17:55

S11	1	S10 and ((silicon si polysilicon poly) same (((etch\$6 dissolv\$6 remov\$6) near4 (liquid base acid basic acidic wet)) with (fluorine fluoride hf hydrofluoric "nh.sub.4f" "nh.sub.4 f") with (hydroxide ammonium tmah "nh.sub.4oh" "nh.sub.4 oh")) same ph)	US-PGPUB; USPAT	OR	ON	2005/12/15 18:00
S15	72	(silicon si polysilicon poly) same ((etch\$6 dissolv\$6 remov\$6) near4 (liquid base acid basic acidic wet)) same (fluorine fluoride hf hydrofluoric "nh.sub.4f" "nh.sub.4 f") same (hydroxide ammonium tmah "nh.sub.4oh" "nh.sub.4 oh") same ph	US-PGPUB; USPAT	OR	ON	2005/12/16 08:04
S16	44	(silicon si polysilicon poly) and ((etch\$6 dissolv\$6 remov\$6) near4 (liquid base acid basic acidic wet)) and (fluorine fluoride hf hydrofluoric "nh.sub.4f" "nh.sub.4 f") and (hydroxide ammonium tmah "nh.sub.4oh" "nh.sub.4 oh") and ph	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/16 08:54